

FORM PTO-1449 JAN 28 2005 INFORMATION DISCLOSURE CITATION IN A TRADE APPLICATION	DOCKET NUMBER DSI 302 ✓	APPLICATION NUMBER 10/815,994 W/816,179
	APPLICANTS Chung J. Lee et al.	
	FILING DATE March 31, 2004	GROUP ART UNIT 2827 1763

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
TA	3,268,599	08/23/1966	Chow	144		
	3,274,267	09/20/1966	Chow	129		
	3,280,202	10/18/1966	Gilch	570	144	
	3,288,728	11/29/1966	Gorham	86		
	3,332,891	07/25/1967	Chow et al.	391		
	3,342,754	09/19/1967	Gorham et al.	386		
	3,349,045	10/24/1967	Gilch	528	397	
	3,379,803	04/23/1968	Tittmann et al.	264	81	
↓	3,503,903	03/31/1970	Shaw et al.	528	396	

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES	NO
TA	EP 0 349 032 A2	01/03/1990	EPO				
	EP 0 523 479 A2	01/20/1993	EPO				
↓	EP 0 856 503 A1	08/05/1998	EPO				

OTHER DOCUMENTS

TA	Chow et al., <i>Poly(a,a,a',a'-tetrafluoro-p-xylylene</i>), <u>Journal of Applied Polymer Science</u> , Vol. 13, No. 9, pp. 2325-2332, 1969.
	Chow et al., <i>The Synthesis of 1,1,2,2,9,9,10,10-octafluorou2, 2Paracyclophane</i> , <u>Journal of Organic Chemistry</u> , Vol. 35, No. 1, pp. 20-22, 1970.
↓	Iwamoto et al., <i>Crystal Structure of Poly-p-xylylene. I. The a Form</i> , <u>Jour. Polymer. Sci. Polymer. Phys. Ed.</u> , Vol. 11, pp. 2403-2411, 1973.

EXAMINER <i>Howard S. Gair</i>	DATE CONSIDERED 11/26/05
-----------------------------------	-----------------------------

FORM PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION		DOCKET NUMBER DSI 302 ✓	APPLICATION NUMBER 10/815,994 10/816,179
		APPLICANTS Chung J. Lee et al.	
		FILING DATE March 31, 2004	GROUP ART UNIT 2827 1763

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
JD	3,509,075	04/28/1970	Niegish et al.	528	390	
	3,626,032	12/07/1971	Norris	526	75	
	3,694,495	09/26/1972	Norris	502	496	
	3,940,530	02/24/1976	Loeb et al.	428	206	
	4,117,308	09/26/1978	Boggs et al.	392	360	
	4,518,623	05/21/1985	Riley	427	8	
	4,823,711	04/25/1989	Kroneberger et al.	110	236	
	4,996,010	02/26/1991	Modrek	604	401	
JD	5,142,023	08/25/1992	Gruber et al.	528	354	

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES	NO
JD	GB 650 947	03/07/1951	Great Britain				
	GB 673 651	06/11/1952	Great Britain				
JD	WO 97/15699	05/01/1997	WIPO				

OTHER DOCUMENTS

	Iwamoto et al., <i>Crystallization During Polymerization of Poly-p-xylene. III. Crystal Structure and Molecular Orientation as a Function of Temperature</i> , <i>Journal of Polymer Science Polymer. Phys. Ed.</i> , Vol. 13, pp. 1925-1938, 1975.
JD	Lee, <i>Transport Polymerization of Gaseous Intermediates and Polymer Crystal Growth</i> , <i>J. Macromol. Sci. Rev. Macromol. Chem.</i> , C16(1), p. 79-127, 1977-78.
JD	Sharma et al., <i>Optimizing Poly(chloro-p-Xylelene) or Parylene C Synthesis</i> , <i>Journal of Applied Science</i> , Vol. 36, No. 7, pp. 1555-1565, Sept. 20, 1988.

EXAMINER <i>John B. Lee</i>	DATE CONSIDERED <i>11/24/05</i>
--------------------------------	------------------------------------

FORM PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION		DOCKET NUMBER DSI 302	APPLICATION NUMBER 10/815,994/0/816,179
		APPLICANTS Chung J. Lee et al.	
		FILING DATE March 31, 2004	GROUP ART UNIT 2827 173

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
✓	5,217,559	06/08/1993	Moslehi et al.	182	345.35	
	5,268,202	12/07/1993	You et al.	427	255.6	
	5,320,518	06/14/1994	Stilger et al.	431	7	
	5,475,080	12/12/1995	Gruber et al.	528	354	
	5,482,009	01/09/1996	Kobayashi et al.	122	367.1	
	5,538,758	07/23/1996	Beach et al.	427	255.6	
	5,572,884	11/12/1996	Christensen et al.	62	476	
	5,639,512	06/17/1997	Nonaka et al.	427	163.2	
✓	5,648,006	07/15/1997	Min et al.	219	464.1	

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES	NO
✓	WO 97/15951	05/01/1997	WIPO				
	WO 97/42356	11/13/1997	WIPO				
✓	WO 99/21705	05/06/1999	WIPO				

OTHER DOCUMENTS

✓	Lee, <i>Polyimides, Polyquinolines and Polyquinoxalines: Tg-Structure Relationships</i> , <u>Journal of Macromolecular Science, Part C – Polymer Reviews</u> (formerly <u>Journal of Macromolecular Science, Part C – Reviews in Macromolecular Chemistry and Physics</u>) Vol. 29(4), p. 431, 1989.
	Lang, <i>Vapor Deposition of Very low k Polymer Films, Poly (Naphthalene), Poly (Fluorinated Naphthalene)</i> , <u>Materials Research Society Symposium Proceedings</u> , Vol. 381, pp. 45-50, April 17, 1995.
✓	Wary et al., <i>Polymer Developed to be Interlayer Dielectric</i> , <u>Semi-Conductor International</u> , pp. 211-216, June 1996.

EXAMINER

Prof. Zain

DATE CONSIDERED

11/26/05

FORM PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION		DOCKET NUMBER DSI 302 ✓	APPLICATION NUMBER 10/815,994 10/816,179
		APPLICANTS Chung J. Lee et al.	
		FILING DATE March 31, 2004	GROUP ART UNIT 2827 1763

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
✓	5,879,808	03/09/1999	Wary et al.	428	411,1	
	5,945,170	08/31/1999	Kozak et al.	427	437	
	5,958,510	09/28/1999	Sivaramakrisham	427	255,6	
	6,051,321	04/18/2000	Lee et al.	428	411,7	
	6,130,171	10/10/2000	Gomi	438	781	
	6,140,456	10/31/2000	Foggiator	528	196	
	6,144,802	11/07/2000	Kim	392	479	
	6,265,320	07/24/2001	Shi et al.	438	728	
✓	6,302,874	10/16/2001	Zhang	604	522	

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES	NO
✓	WO 99/21706	05/06/1999	WIPO				
	WO 99/21924	05/06/1999	WIPO				
✓	WO 99/22043	05/06/1999	WIPO				

OTHER DOCUMENTS

✓	Wunderlich, <i>Crystal Nucleation, Growth, Annealing, Macromolecular Physics</i> , Vol. 1-2, pp. 242-243, 246-247, 1996.
	Greiner, <i>Poly(1,4-xylylene)s: Polymer Films by Chemical Vapour Deposition</i> , <i>Trends in Polymer Science</i> , Vol. 5, No. 1, pp. 12-16, 1997.
✓	Harrus et al., <i>Parylene Af-4: A Low ϵ_R Material Candidate for ULSI Multilevel Interconnect Applications</i> , <i>Material Research Society Symposium Proceedings</i> , Vol. 443, 1997.

EXAMINER <i>Chung J. Lee</i>	DATE CONSIDERED 11/26/05
---------------------------------	-----------------------------

FORM PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION		DOCKET NUMBER DSI 302 ✓	APPLICATION NUMBER 10/815,994 10/816,179
		APPLICANTS Chung J. Lee et al.	
		FILING DATE March 31, 2004	GROUP ART UNIT 2827 763

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
	6,703,462	03/09/2004	Lee	526	242	
	6,797,343	09/28/2004	Lee	428	1,1	
	2002/0050659	05/02/2002	Toreki et al.	264	4,1	
	2002/0120083	08/29/2002	Lee	526	242	
	2003/0051662	03/20/2003	Lee	118	50	
	2003/0072947	04/17/2003	Lee	428	421	
	2003/0143341	07/31/2003	Lee	428	1,1	
✓	2003-0188683	10/9/2003	Lee	118	82,1	
✓	2003-0195312	10/16/2003	Lee	526	242	

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES	NO

OTHER DOCUMENTS

✓	Plano et al., <i>The Effect of Deposition Conditions on the Properties of Vapor-Deposited Parylene Af-4 Films</i> , <u>Material Research Society Symposium Proceedings</u> , Vol. 476, pp. 213-218, 1997.
	Ryan et al., <i>Effect of Deposition and Annealing on the Thermomechanical Properties of Parylene Films</i> , <u>Material Research Society Symposium Proceedings</u> , Vol. 476, pp. 225-230, 1997.
	Yang et al., <i>High Deposition Rate Parylene Films</i> , <u>Journal of Crystal Growth</u> , Vol. 183, No. 3, pp. 385-390, 1998.
✓	Mathur et al., <i>Vapor Deposition of Parylene-F Using Hydrogen as Carrier Gas</i> , <u>Journal of Materials Research</u> , Vol. 14, No. 1, pp. 246-250, 1999.

EXAMINER

DATE CONSIDERED

11/26/05

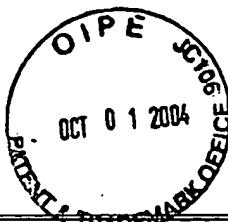
FORM PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION	DOCKET NUMBER DSI 302 ✓	APPLICATION NUMBER 10/815,994 10/816,179
	APPLICANTS Chung J. Lee et al.	
	FILING DATE March 31, 2004	GROUP ART UNIT 2827 1763

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS

<i>D/S</i>	Morgen et al., <i>Morphological Transitions in Fluorinated and Non-Fluorinated Parylenes</i> , <u>Material Research Society Symposium Proceedings</u> , Vol. 565, pp. 297-302, 1999.
	Brun, <i>100nm: The Undiscovered Country</i> , <u>Semiconductor International</u> , p. 79, February 2000.
	Peng and McGivern, <i>Quantum Yields and Energy Partitioning in the UV Photodissociation of Halon 2402</i> , <u>Journal of Chemical Physics</u> , Vol. 113, No. 17, pp. 7149-7157, 2000.
<i>V</i>	Rashed, <i>Properties and Characteristics of Silicon Carbide</i> , website publication (www.poco.com), POCO Graphite Inc., 2002.



SHEET 1 OF 1

FORM PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION		DOCKET NUMBER DSI 302	APPLICATION NUMBER 10/816,179
		APPLICANTS Chung J. Lee et al.	
		FILING DATE March 31, 2004	GROUP ART UNIT 1763

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL DATE IF APPROP.
<i>De</i>	3,503,903	3/31/70	Shaw et al.	528	396	
	6,086,952	7/11/00	Lang et al.	427	255.29	
	6,130,171	10/10/00	Gomi		781	
	6,265,320	7/24/01	Shi et al.		725	
	6,455,443	9/24/02	Eckert et al.	438	781	
<i>De</i>	6,495,208	12/17/02	Desu et al.	427	255.31	

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES	NO

OTHER DOCUMENTS

	<i>De</i>	<i>Parylene Copolymers</i> , Taylor et al., <u>Low Dielectric Constant Materials III</u> , pp. 197-205, 1997.
	<i>De</i>	<i>Finer Copper Wires Make for Faster Integrated Circuits</i> , Preuss, <u>Research News</u> , pp. 1-3, April 5, 1999.
	<i>De</i>	<i>Study of Hydrogen Annealing of Ultrahigh Molecular Weight Polyethylene Irradiated with High-Energy Protons</i> , Wilson et al., <u>Journal of Materials Research</u> , Vol. 14, No. 11, November 1999.
	<i>De</i>	<i>A Novel Oxazole Based Low k Dielectric Addresses Copper Damascene Needs</i> , Schmid et al., <u>Semiconductor Fabtech</u> , 12 th Edition, pp. 231-235, July 2000.
	<i>De</i>	<i>The Effect of Water Desorption and Organosilane Coupling Agents on the Adhesion of Poly(p-xylylene) Films to a Silicon Wafer Surface</i> , Lightfoot et al., <u>Journal of Materials Science: Materials in Electronics</u> , Vol. 12, pp. 581-586, 2001.
	<i>De</i>	<i>Current Technical Trends: Dual Damascene & Low-k Dielectrics</i> , Healey on behalf of Threshold Systems, pp. 1-6, © 2002.

EXAMINER	<i>De</i>	DATE CONSIDERED	<i>11/20/05</i>
----------	-----------	-----------------	-----------------